	Hits	Search Text	DBs
34	8	((resist or photoresist) near16 pattern$4 near29 mask) and ((post$3imag$4 or expos$4 or irradiat$4 or illuminat$4) near12 strip$4 near16 ((resist or photoresist) near6 (pattern$3 or mask)) near12 (residu$4 or remain$4)) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive) near26 electrode) same (substrate or device or wafer) same (resist or photoresist) same pattern)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
35	124	((resist or photoresist) near16 pattern$4 near29 mask) and ((post$3imag$4 or expos$4 or irradiat$4 or illuminat$4 or post$4expos$5 or post$8develop$5) near12 (remov$4 or strip$4) near16 ((resist or photoresist) near6 (pattern$3 or mask)) near16 (residu$4 or remain$4 or remnant)) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive) near26 electrode) same (substrate or device or wafer) same (resist or photoresist) same pattern$3 same (etch$4 or RIE))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
36	18	((resist or photoresist) near16 pattern$4 near29 mask) and ((post$3imag$4 or expos$4 or irradiat$4 or illuminat$4 or post$4expos$5 or post$8develop$5) near12 (strip$4) near16 ((resist or photoresist) near6 (pattern$3 or mask)) near16 (residu$4 or remain$4 or remnant)) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive) near26 electrode) same (substrate or device or wafer) same (resist or photoresist) same pattern$3 same (etch$4 or RIE))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
37	1	((resist or photoresist) near16 pattern$4) and ((post$3imag$4 or expos$4 or irradiat$4 or illuminat$4 or post$4expos$5 or post$8develop$5) near16 ((resist or photoresist) near26 (pattern$3 or mask)) near16 (residu$4 or remain$4 or remnant)) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive) near26 electrode) same (substrate or device or wafer) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone)) and strip$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
38	3	((resist or photoresist) near16 pattern$4) and ((post$3imag$4 or expos$4 or irradiat$4 or illuminat$4 or post$4expos$5 or post$8develop$5) near16 ((resist or photoresist) near26 (pattern$3 or mask))) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive) near26 electrode) same (substrate or device or wafer) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone)) and strip$4 and residu$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
39	45	S45 NOT S44	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
40	12	((resist or photoresist) near16 pattern$4) and ((post$3imag$4 or expos$4 or irradiat$4 or illuminat$4 or post$4expos$5 or post$8develop$5) near16 ((resist or photoresist) near26 (pattern$3 or mask))) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive) near26 electrode) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone)) and strip$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
41	42	(((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate) near26 electrode) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone) same (photoresist or resist)) and ((expos$4 or illuminat$4 or irradiat$4) near5 (time or seconds or minute))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
42	23	(((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate)) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone) same (photoresist or resist) same ((expos$4 or illuminat$4 or irradiat$4) near5 (time or "seconds" or minute)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
43	13	((resist or photoresist) near16 pattern$4) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate) near26 electrode) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone) same (photoresist or resist)) and strip$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
44	58	((resist or photoresist) near16 pattern$4) and (((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate) near26 electrode) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone) same (photoresist or resist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
45	27	(((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate) near26 electrode) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone) same (photoresist or resist) same (expos$4 or illuminat$4 or irradiat$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
46	6	(((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate) near26 electrode) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE)) and ((photosensitizer or DNQ or diazonaphthoquinone) same (photoresist or resist) same (expos$4 or illuminat$4 or irradiat$4) same (PEB or post$4imag$4 or post$4expos$6))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB